IEUVI Optics Contamination and Lifetime TWG February 19, 2006

#	Item		Start Time	End Time
1	**Welcome / Registration**	**15**	9:45 AM	10:00 AM
2	Cap Layer Development Technology Mapping, led by Ming Fang (Intel Corp.)	**60**	10:00 AM	11:00 AM
3	in situ Metrology Technology Mapping, led by Shannon Hill (NIST) & Obert Wood (AMD/ SEMATECH)	**60**	11:00 AM	12:00 PM
4	Lunch	**60**	12:00 PM	1:00 PM
5	Lifetime Testing: past plans, current status, ideal test chamber led by Ginger Edwards (Freescale/ SEMATECH) & Manish Chandhok (Intel Corp.)	**60**	1:00 PM	2:00 PM
6	Beta Specs Revisited, led by Ginger Edwards (Freescale/ SEMATECH)	**30**	2:00 PM	2:30 PM
7	Critical Issue Voting Revisited, led by Ginger Edwards (Freescale/ SEMATECH)	**30**	2:30 PM	3:00 PM
8	Break	**15**	3:00 PM	3:15 PM
9	Invited Talk: Paul Kirsch (IBM/ SEMATECH FEP Division): “High K Gate Materials Development & Metrology: Applicable Lessons for EUV Optics Cap Layer Development”	**30**	3:15 PM	3:45 PM
10	Invited Talk: Alain Diebold (Senior Fellow, SEMATECH): “Post-lifetime Testing Metrology for EUV Optics Cap Layers”	**30**	3:45 PM	4:15 PM
11	Invited Talk: Tim Hossain (Cerium Labs): “Sample Handling Issues and Related Metrology for EUV Optics Cap Layers”	**30**	4:15 PM	4:45 PM
12	Break	**10**	4:45 PM	4:55 PM
13	US Update: Tom Lucatorto, NIST	**20**	4:55 PM	5:15 PM
14	Japan Update: Yasuaki Fukuda, EUVA	**20**	5:15 PM	5:35 PM
15	Wrap / Assignment Action Items	**10**	5:35 PM	5:45 PM